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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/853,467	05/11/2001	Terry Lee Bray	30705-68918	6692
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Barnes & Thornburg 11 South Meridian Street Indianapolis, IN 46204		EXAMINER SONG, MATTHEW J		
		ART UNIT 1765		

DATE MAILED: 12/09/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

09/853,467

Applicant(s)

BRAY, TERRY LEE

Examiner

Matthew J Song

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-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 24 September 2003.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1,2,4,5 and 14-41 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1,2,4,5 and 14-41 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. §§ 119 and 120

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
* See the attached detailed Office action for a list of the certified copies not received.
- 13) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application) since a specific reference was included in the first sentence of the specification or in an Application Data Sheet. 37 CFR 1.78.
a) ☐ The translation of the foreign language provisional application has been received.
- 14) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121 since a specific reference was included in the first sentence of the specification or in an Application Data Sheet. 37 CFR 1.78.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☐ Information Disclosure Statement(s) (PTO-1449) Paper No(s) _____
- 4) ☐ Interview Summary (PTO-413) Paper No(s). _____
- 5) ☐ Notice of Informal Patent Application (PTO-152)
- 6) ☐ Other:

DETAILED ACTION

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 9/24/2003 has been entered.

Claim Objections

2. Claim 5 is objected to because of the following informalities: Claim 5 recites, "the reservoir solution the material proved to affect vapor diffusion rates" in lines 2-3. The Examiner recommends separates the two ideas using a period or a comma to improve the grammar. Appropriate correction is required.

3. Claim 34 is objected to because of the following informalities: Claim 34 recites, "the collar having a width large than the diameter of the well" in line 2. The Examiner recommends replacing "large" with "larger" to improve the grammar. Appropriate correction is required.

Claim Rejections - 35 USC § 103

4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person

having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

5. Claims 1-2, 4-5, 14-23 and 27-31, 36-39 are rejected under 35 U.S.C. 103(a) as being unpatentable over Heilig et al (US 5,266,284) in view of Knittel (US 3,972,689).

Heilig et al discloses a means of which the direction and amount of diffusion can be controlled by the degree of overlap of a gap and reservoirs, where three housing parts **106**, **102**, **112** with **112** being rotatably disposed with respect to a center part **102**. Heilig et al also discloses a protein solution **107** is situated in a glass cylinder **105** (col 4, ln 30-68). Heilig et al also discloses two recesses **96** are situated in a wall of the center part which borders on a rotating part **112**, this reads on applicant's selection unit, two reservoirs **130**, **132** are disposed in indentations inside the rotating part **112** and a component **122**, this reads on applicant's cover (Fig 14a). Heilig et al also discloses a sealing washer **92** is arranged between the rotating and the center part and the washer has recesses **93** which corresponds to those of **96** in the wall of the center part. Heilig et al also discloses for the crystallization phase, the rotating part is rotated so far the one of the reservoirs comes to be situated completely or partially over the recesses **96** and as a result diffusion can take place from or to a drop of protein solution **107** (col 5, ln 1-55 and Figs 14-17). Heilig et al also discloses a "hanging drop" method of crystal growth (col 1, ln 15-25).

Heilig et al discloses a reservoir solution and a channel **96**, which allows diffusion to take place when the reservoir are situated over the recesses **96**. Heilig et al does not disclose a device having a first end, a second end, and a discrete diffusion pathway extending from the first end to

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the second and first end is configured for placement in a well of a plate containing the reservoir solution.

In a method of vapor growing crystals, note entire reference, Knittel teaches a diffusion limiting channel having a first end, a second end and a discrete diffusion pathway 4 extending from the first end to the second end and the first end of the device configured for placement in a well containing a reservoir solution 5. The diffusion limiting channel provides the only pathway between a source and a growing crystal. Knittel also teaches the limiting channel can take forms such as a single capillary tube, several capillary tubes or any other shapes 6,7,8. Knittel also teaches the diffusion limiting channels produces crystal of superior quality and allows improved stoichiometric control. It would have been obvious to a person of ordinary skill in the art at the time of the invention to modify Heilig et al vapor diffusion device with Knittel's diffusion limiting channel between a source and a growing crystal to grow crystals of superior quality and to improve stoichiometric control.

Referring to claim 2, the combination of Heilig et al and Knittel teach discrete channels 4.

Referring to claim 4, the combination of Heilig et al and Knittel teach the extent of diffusion can be controlled by the degree of overlap and the rotating part is rotated so far the one of the reservoirs comes to be situated completely or partially over the recesses, this reads on applicant's actively controlled channel unit.

Referring to claim 5, the combination of Heilig et al and Knittel teach the limiting channels can be fine holes drilled through a plug ('689 col 1, ln 39-45), this reads on applicant's material porous to vapor, where the material is proved to affect vapor diffusion rates.

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Referring to claim 14, the combination of Heilig et al and Knittel teach reservoirs **130** and **132**, this reads on applicant's reservoir unit comprising a plurality of reservoir chambers, a plurality of diffusion limiting channel **7**, this reads on applicant's channel unit, and a rotating part **112**, this reads on applicant's selection unit with a opening (Figs 14-17) and the rotating part is rotated so far the one of the reservoirs comes to be situated completely or partially over the recesses **96** to control the amount of diffusion (col 4, ln 55 to col 5, ln 45). The combination of Heilig et al and Knittel is silent to the opening is large enough not to control the rate of vapor diffusion. It is inherent to the invention taught by the combination of Heilig et al and Knittel to have an opening large enough not to control the rate of vapor diffusion because opening is as large as the reservoir opening (Fig 14b), therefore can not control the rate of vapor diffusion. Also, the combination of Heilig et al and Knittel teaches the rotating part **112** is rotatable. The combination of Heilig et al and Knittel is silent to the channel unit can rotate. However, the combination of Heilig et al and Knittel teaches the channel unit is a separate housing part, which is inherently capable of being rotated. The combination of Heilig et al and Knittel is not required to have the channel unit rotate, merely the capability of being rotated. The combination of Heilig et al and Knittel is silent to each channel having a different geometry different from each other to provide different diffusion rates. However, the combination of Heilig et al and Knittel teach other shapes can be used and the cross-sectional area of a capillary tube affects the quality of the crystal. Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to modify the combination of Heilig et al and Knittel by optimizing the geometry of each capillary tube to obtain same by conducting routine experimentation of a result effective variable (MPEP 2144.05).

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Referring to claim 15, the combination of Heilig et al and Knittel teach a cover, **122** (Fig 14a).

Referring to claim 16, the combination of Heilig et al and Knittel silent to the channel unit comprises an opening large enough not to control the rate of vapor diffusion. It is inherent to the invention taught by the combination of Heilig et al and Knittel to have an opening large enough not to control the rate of vapor diffusion because the opening is as large as the reservoir opening, therefore can not control the rate of vapor diffusion (Fig 14b).

Referring to claim 17, the combination of Heilig et al and Knittel teach a sealing washer **92**.

Referring to claim 18, the combination of Heilig et al and Knittel teach the extent of diffusion can be controlled by the degree of overlap and the rotating part is rotated so far the one of the reservoirs comes to be situated completely or partially over the recesses, this reads on applicant's actively controlled channel unit.

Referring to claim 19 the combination of Heilig et al and Knittel teach a solution is situated in a glass cylinder **105**, this reads on applicant's container. A diffusion limiting channel **4**, this reads on applicant's device having discrete diffusion pathways and sealing with O-rings **104**, **120** and a sealing washer **92**, this reads on applicant's seal. The combination of Heilig et al and Knittel teach a lid **122** (Fig 14a), which also reads on applicant's seal.

Referring to claim 20, the combination of Heilig et al and Knittel teach a diffusion limiting channel **4,7**, this reads on applicant's discrete channels. (col 5, ln 1-15)

Referring to claim 21, the combination of Heilig et al and Knittel teach two recesses **96** and two reservoir solutions **130**, **132**. (col 5, ln 1-15)

Referring to claim 22, the combination of Heilig et al and Knittel teach the extent of diffusion can be controlled by the degree of overlap and the rotating part is rotated so far the one of the reservoirs comes to be situated completely or partially over the recesses, this reads on applicant's actively controlled channel unit.

Referring to claim 23, the combination of Heilig et al and Knittel teach the limiting channels can be fine holes drilled through a plug ('689 col 1, ln 39-45), this reads on applicant's material porous to vapor, where the material is proved to affect vapor diffusion rates.

Referring to claim 28-29, the combination of Heilig et al and Knittel teaches the channel unit is a separate housing part from the first housing part 106, which is inherently capable of being removable. Furthermore, making elements separable was held to have been obvious (MPEP 2144.04 and In re Dulberg 129 USPQ 148 (CCPA 1961)).

Referring to claims 30-31, 37 and 38, the combination of Heilig et al and Knittel teaches sealing with O-rings 104, 120 and a sealing washer 92 (col 5, ln 1-5).

Referring to claims 33 and 39, the combination of Heilig et al and Knittel is silent to the length of the diffusion channel. The length of a diffusion channel and cross sectional area affect diffusion rate, as evidenced by Roorda et al (US 5,972,369) below. Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to modify the combination of Heilig et al and Knittel by optimizing the length of the channel to obtain same by conducting routine experimentation of a result effective variable (MPEP 2144.05). Furthermore, changes in size and shape is held to be obvious (MPEP 2144.04)

Referring to claim 36, the combination of Heilig et al and Knittel teaches a first end for a growth solution **107**, a second end for a reservoir solution **130, 132**, a cylindrical body extending from the first end to the second end **96** and a diffusion pathway **4**.

6. Claims 24-26, 32, 34, 35 40-41 rejected under 35 U.S.C. 103(a) as being unpatentable over Heilig et al (US 5,266,284) in view of Knittel (US 3,972,689) as applied to claims 1-2, 4-5, 14-23 and 27-31 above, and further in view of Kim et al (US 6,039,804).

The combination of Heilig et al and Knittel teach all of the limitations of claim 24, as discussed previously, except the seal is optically clear.

In a method of hanging drop crystallization of a protein, note entire reference, Kim et al teaches a drop of solution containing the substance to be crystallized to a cover slip **46**, which is inserted into a drop chamber. Kim et al also teaches after the solution is placed in the drop chamber the drop chamber can be sealed by applying a sealant, preferably transparent, adhesive tape (col 4, ln 45-67), this reads on applicant's optically clear. Kim et al also teaches a crystallization tray which includes 24 crystallization units (col 5, ln 55-65). Referring to claim 32, the combination of Kim et al and Knittel teaches hanging drop crystallization by applying drop of solution to a cover slip **46** ('804 col 4, ln 45-65). Knittel teaches a collar **14** adjacent the second end having a width larger than the diameter of the well. It would have been obvious to a person of ordinary skill in the art at the time of the invention to modify the combination of Heilig et al and Knittel with Kim et al's transparent means of sealing a chamber to observe the crystallization process.

7. Claims 1, 2, 4, 5, 29-41 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kim et al (US 6,039,804) in view of Knittel (US 3,972,689).

Kim et al discloses a crystallization unit **26** includes a central reservoir **28**, four diffusion channels **30** and four drop chambers **32**.

Kim et al does not disclose a device having a first end, a second end and the first end of the device configured for placement in a well of a plate containing the reservoir solution.

In a method of vapor growing crystals, note entire reference, Knittel teaches a diffusion limiting channel having a first end, a second end and a discrete diffusion pathway **4** extending from the first end to the second end and the first end of the device configured for placement in a well containing a reservoir solution **5**. The diffusion limiting channel provides the only pathway between a source and a growing crystal. Knittel also teaches the limiting channel can take forms such as a single capillary tube, several capillary tubes or any other shapes **6,7,8**. Knittel also teaches the diffusion limiting channels produces crystal of superior quality and allows improved stoichiometric control. It would have been obvious to a person of ordinary skill in the art at the time of the invention to modify Kim et al vapor diffusion device with Knittel's diffusion limiting channel between a source and a growing crystal to grow crystals of superior quality and to improve stoichiometric control.

Referring to claims 2 and 20, the combination of Kim et al and Knittel teach several capillary tubes ('689 col 1, ln 35-45), this reads on applicant's discrete channels.

Referring to claims 4 and 22, the combination of Kim et al and Knittel teach diffusion between the reservoir and the drop chambers can be terminated by deposition of a vapor

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impermeable substrate in the diffusion channel ('804 col 5, ln 15-25), this reads on applicant's channel size can be actively controlled.

Referring to claims 5 and 23, the combination of Kim et al and Knittel teach the limiting channels can be fine holes drilled through a plug ('689 col 1, ln 39-45) and a vapor diffusive reagent may be deposited in the drop chamber to control the crystallization process ('804 col 7, ln 10-20), this reads on applicant's material porous to vapor, where the material is proved to affect vapor diffusion rates.

Referring to claim 19, the combination of Kim et al and Knittel teach a container for holdn a reservoir solution **28**, a device configured fro engaging the container, the device having a first end configured for placement within the container, a second end and a discrete diffusion pathway extending from the first end to the second end **4**, a seal configured to engage the second end, wherein the seal engages the second end; the seal and the second end define a space for crystal growth solution ('804 col 4, ln 45-67).

Referring to claim 20, the combination of Kim et al and Knittel teach a second reservoir solution ('804 Fig 1).

Referring to claims 24-26 and 41, the combination of Kim et al and Knittel teach a drop of solution containing the substance to be crystallized to a cover slip **46**, which is inserted into a drop chamber. Kim et al also teaches after the solution is placed in the drop chamber the drop chamber can be sealed by applying a sealant, preferably transparent, adhesive tape ('804 col 4, ln 45-67), this reads on applicant's optically clear.

Referring to claim 27-29, the combination of Kim et al and Knittel does not explicitly teach the parts are removable. This is inherent because the combination of Kim et al and Knittel

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teach a plug ('689 col 1, ln 35-45), which is removable. Furthermore, making elements separable was held to have been obvious (MPEP 2144.04 and In re Dulberg 129 USPQ 148 (CCPA 1961)).

Referring to claims 30-31, 37, the combination of Kim et al and Knittel is silent to an O-ring. However, O-ring are well known in the art to be used as a sealing means in vapor diffusion processes, as evidenced by Heilig et al (US 5,266,284).

Referring to claim 32, the combination of Kim et al and Knittel teaches a hanging drop crystallization by applying drop of solution to a cover slip 46 ('804 col 4, ln 45-65).

Referring to claims 33 and 39, the combination of Kim et al and Knittel is silent to the length of the diffusion channel. The length of a diffusion channel and cross sectional area affect diffusion rate, as evidenced by Roorda et al (US 5,972,369) below. Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to modify the combination of Kim et al and Knittel by optimizing the length of the channel to obtain same by conducting routine experimentation of a result effective variable (MPEP 2144.05). Furthermore, changes in size and shape is held to be obvious (MPEP 2144.04)

Referring to claim 34, the combination of Kim et al and Knittel teaches a collar 14 adjacent the second end having a width larger than the diameter of the well.

Referring to claim 35 and 40, the combination of Kim et al and Knittel teaches a 24 crystallization units 26 ('804 col 5, ln 55-65 and Fig 7).

Referring to claim 36, the combination of Kim et al and Knittel teaches a first depression to provide a space 40, a second end for placement into a well of a plate, the well containing a reservoir solution 28, a generally cylindrical body extending from the first end to the second end ('804 Fig 3) and a diffusion pathway 4.

Response to Arguments

8. Applicant's arguments with respect to claims 1-2, 4-5, 14-23, and 27-31 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

9. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Roorda et al (US 5,972,369) teaches a capillary channel has a cross sectional area and a length selected to deliver material at a predetermined rate (col 2, ln 15-25).

10. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Matthew J Song whose telephone number is 703-305-4953. The examiner can normally be reached on M-F 9:00-5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 703-305-2667. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0661.

Matthew J Song
Examiner
Art Unit 1765

MJS

SUPERVISOR
NADINE G. NORTON
PRIMARY EXAMINER

